

Pat	App No.	Pub No.	Class	Date Filed	Inventor Name	Title
	08071341		101	05/07/00	DAVIS, TODD	Method and system for preparing a pattern
	08071344		101	05/21/00	DAVIS, TODD	Method and system for preparing a pattern
	08071347		101	05/18/00	DAVIS, TODD	Method and system for preparing a pattern
	10043984		030	09/17/00	DAVIS, TODD	Adaptive lithographic critical dimension enhancement
	10043987		030	10/10/00	DAVIS, TODD	Methods to improve resolution of cross sectioned features created using an ion beam
	10071781		093	11/21/00	DAVIS, TODD	METHOD FOR DEVELOPING A PHOTORESIST PATTERN
	10071783		030	12/10/00	DAVIS, TODD	Integrated lithographic fabrication cluster















Pat	App Num	Pub Num	Class	Date Filed	Inventor Name	Title
	09071941		154	09/07/2004	DAVIS, TODD	Adaptation of piezoelectric
	09723184		151	09/21/2004	DAVIS, TODD	Acoustic sensing instruments
	09725193		151	09/18/2004	DAVIS, TODD	Anti-hijacking cockpit door system for aircraft
	10563964		030	09/17/2003	DAVIS, TODD	Adaptive lithographic critical dimension enhancement
	10582445		030	10/10/2003	DAVIS, TODD	Methods to improve resolution of cross sectioned features created using an ion beam
	10717813		093	11/21/2003	DAVIS, TODD	METHOD FOR DEVELOPING A PHOTORESIST PATTERN
	10731430		030	12/10/2003	DAVIS, TODD	Integrated lithographic fabrication cluster



	Type	L#	Hits	Search Text	DBs	Time Stamp	Comments	Error	Definition	Er
1	IS&R	L1	6	(("5229872") or ("5296891") or ("5523193") or ("5969441") or ("6046792") or ("20020081758")).PN	US-P GPUB:06:21  USPA T	2004/12/13				
2	BRS	L2	0	1 and substrate and attribut\$3 and exposure and lithograph\$3	US-P GPUB:06:22  USPA T	2004/12/13				
3	BRS	L3	0	1 and substrate and attribut\$3 and expos\$3 and lithograph\$3	US-P GPUB:06:22  USPA T	2004/12/13				
4	BRS	L4	0	1 and substrate and attribut\$3 and expos\$3	US-P GPUB:06:23  USPA T	2004/12/13				
5	BRS	L5	26	substrate and attribut\$3 and expos\$3 and lithograph\$3 and uniform and regulat\$3 and dosage	US-P GPUB:06:24  USPA T	2004/12/13				



U.S. Patent	Document ID	Issue Date	Pages	Title	Current OR	Current XR	Retrieval C	Inventor	S	C	P	J			
1	US 5510628 A	19960423	20	Deep ultraviolet photolithographically defined ultra-thin films for selective cell adhesion and outgrowth and method of manufacturing the same and devices containing the same	257/32	257/37; 257/E21.174; 257/E21.175; 430/315; 435/29; 438/1		Georger, Jr.; Jacque H. et al.			P	P	P	P	P
2	US 5324591 A	19940628	21	Deep ultraviolet photolithographically defined ultra-thin films for selective cell adhesion and outgrowth and method of manufacturing the same and devices containing the same	428/552	257/E21.174; 257/E21.175; 428/336; 430/296; 438/1		Georger, Jr.; Jacque H. et al.			P	P	P	P	P
3	US 5079600 A	19920107	17	High resolution patterning on solid substrates	257/750	257/629; 257/E21.174; 257/E21.175; 427/553; 427/558; 427/97.4; 430/314; 430/315; 438/669; 438/694		Schnur, Joel M. et al.			P	P	P	P	P
4	US 20040171038 A1	20040902	102	IL-1 gene cluster and associated inflammatory polymorphisms and haplotypes	435/6			Nicklin, Martin et al.			P	P	P	P	P
5	US 20040142974 A1	20040722		4,4-disubstituted piperidines, and methods of use thereof	514/326	514/317; 546/207; 546/236		Hoemann, Michael Z.			P	P	P	P	P
6	US 20040077090 A1	20040422		Whole cell engineering by mutagenizing a substantial portion of a starting genome, combining mutations, and optionally repeating	435/471	435/252.3; 435/254.2		Short, Jay M.			P	P	P	P	P
7	US 20040067512 A1	20040408		Single nucleotide polymorphisms and mutations on Alpha-2-Macroglobulin	435/6			Becker, Kenneth David et al.			P	P	P	P	P
8	US	20040219		Polymorphisms of PD-1	435/6	536/23.2		Alarcon-Riquelme,							



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U	Document ID	Issue Date	Pages	Title	Current OR	Current XR	Retrieval C	Inventor	S	C	P	3	3
1	US 6046792 A	20000404	30	Differential interferometer system and lithographic step-and-scan apparatus provided with such a system	355/53	356/490; 356/493; 356/500; 356/509		Van Der Werf, Jan E. et al.					
2	US 5969441 A	19991019	20	Two-dimensionally balanced positioning device with two object holders, and lithographic device provided with such a positioning device	310/12	248/178.1; 74/480R		Loopstra, Erik R. et al.					
3	US 20020081758 A1	20020627	44	Method of manufacturing semiconductor integrated circuit device	438/16	257/E21.525		Iriki, Nobuyuki					
4	US 5523193 A	19960604	7	Method and apparatus for patterning and imaging member	430/311	346/107.1; 347/134; 358/300; 430/20		Nelson, William E.					
5	US 5296891 A	19940322	9	Illumination device	355/67	347/258; 355/53		Vogl, Holger et al.					
6	US 5229872 A	19930720	6	Exposure device including an electrically aligned electronic mask for micropatterning	349/2	349/116; 349/25; 355/20; 430/22		Mumola, Peter B.					